

| | Search Text |
|----|---|
| 1 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) sane (residu\$3 chamber)) |
| 2 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and etch\$3 |
| 3 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and plasma |
| 4 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)) |
| 5 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and etch\$3 |
| 6 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and plasma |
| 7 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3) |
| 8 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and etch\$3) (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) |
| 9 | first adj cleaning adj (gas compound mixture agent) |
| 10 | first adj cleaning adj gas |
| 11 | second adj cleaning adj gas |
| 12 | (first adj cleaning adj gas) (second adj cleaning adj gas) |
| 13 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and ((first adj cleaning adj gas) (second adj cleaning adj gas)) |
| 14 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") and ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr) |
| 15 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr) |
| 16 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and etch\$3) (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber)))) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr))) |

| | Search Text |
|----|---|
| 17 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber))) and etch\$3) (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber))) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr))) and silicide |
| 18 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber))) and etch\$3) (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) sane (residu\$3 chamber))) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr))) and silicide) and (etch\$3 near residue) |
| 19 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) same (residu\$3 chamber)) |
| 20 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) same (residu\$3 chamber))) and etch\$3 |
| 21 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) same (residu\$3 chamber))) and plasma |
| 22 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber) |
| 23 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and etch\$3 |
| 24 | ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and plasma |
| 25 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and etch\$3) OR (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr))) |
| 26 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and etch\$3) OR (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr)))) and silicide |
| 27 | (((((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and etch\$3) OR (((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber)) and plasma)) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3))) and ((("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr)))) and silicide) and (etch\$3 near residue) |
| 28 | (clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3)) |
| 29 | ((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma |
| 30 | ((((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma) and (power near2 (plasma RF source) near2 (chang\$3 vary\$3 decreas\$3 increas\$3 modify\$3 adjust\$3 raising lowering)) |

| | Search Text |
|----|--|
| 31 | (((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma) and (power near2 (plasma RF source) near2 (chang\$3 vary\$3 decreas\$3 increas\$3 modify\$3 adjust\$3 raising lowering))) and (bias\$3 near3 (off zero "0" no\$1)) |
| 32 | (((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma) and (power near2 (plasma RF source) near2 (chang\$3 vary\$3 decreas\$3 increas\$3 modify\$3 adjust\$3 raising lowering))) and (chamber near2 bias\$3 near3 (off zero "0" no\$1)) |
| 33 | ((("6123862") or ("6071372") or ("5961793") or ("5877032") or ("5817534") or ("5654679") or ("5180464")).PN |
| 34 | ((("6123862") or ("6071372") or ("5961793") or ("5877032") or ("5817534") or ("5654679") or ("5180464")).PN) and (((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma) and (power near2 (plasma RF source) near2 (chang\$3 vary\$3 decreas\$3 increas\$3 modify\$3 adjust\$3 raising lowering))) and (bias\$3 near3 (off zero "0" no\$1)) |
| 35 | (((clean\$3 near3 (chamber residu\$3 reactor deposit\$3 plasma)) (remov\$3 near3 (residu\$3 deposit\$3))) and etch\$3 and plasma) and (power near2 (plasma RF source) near2 (chang\$3 vary\$3 decreas\$3 increas\$3 modify\$3 adjust\$3 raising lowering))) and (chamber near2 bias\$3 near3 (off zero "0" no\$1)) |
| 36 | (chamber near clean\$3) and (increas\$3 near (power energy)) |
| 37 | ((chamber near clean\$3) and (chamber near bias\$3)) and ((chamber near clean\$3) same (increas\$3 near (power energy))) |
| 38 | (chamber near clean\$3) same (increas\$3 near (power energy)) |

| | Hits | Search Text |
|---|------|---|
| 1 | 150 | (etch\$3 near (Si silicon polysilicon poly-Si)) same ("SF.sub.6" same ("CHF.sub.3" "CF.sub.3 H")) |
| 2 | 0 | 1 same (ICP inductive\$3) |
| 3 | 11 | 1 and (ICP inductive\$3) |
| 4 | 78 | etch\$3 near (silicon si polysilicon poly-Si) same (ICP inductive\$3) |
| 5 | 4 | 1 and 4 |
| 6 | 0 | 5 not 3 |
| 7 | 9 | (etch\$3 near (Si silicon polysilicon poly-Si)) same ("SF.sub.6" near ("CHF.sub.3" "CF.sub.3 H")) |
| 8 | 6 | 7 not 3 |

| | Search Text |
|---|---|
| 1 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") near5 ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr) |
| 2 | 1 and electrostatic adj chuck |
| 3 | 2 and ((polycide silicide) near (nitride oxide (hard adj mask))) |
| 4 | 1 and ((polycide silicide) near (nitride oxide (hard adj mask))) |
| 5 | 4 and clean\$3 |
| 6 | 5 6 |
| 7 | 4 and (remov\$3 near (residue deposit\$3)) |

| | Search Text |
|----|---|
| 1 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) same (residu\$3 chamber)) |
| 2 | 1 and etch\$3 |
| 3 | 1 and plasma |
| 4 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same ((clean\$3 remov\$3) same (residu\$3 chamber)) |
| 5 | 4 and etch\$3 |
| 6 | 4 and plasma |
| 7 | (5 6) and (("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3)) and (("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr)) |
| 8 | 7 and silicide |
| 9 | 8 and (etch\$3 near residue) |
| 10 | (chamber near clean\$3) and (chamber near bias\$3) |

| | Hits | Search Text | DBs |
|---|------|--|---|
| 1 | 3896 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") and ((clean\$3 remov\$3) same (residu\$3 chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 2 | 3074 | 1 and etch\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 3 | 3004 | 1 and plasma | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 4 | 1232 | ("CF.sub.4" "SF.sub.6" "NF.sub.3") same (clean\$3 remov\$3) same (residu\$3 chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 5 | 1097 | 4 and etch\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 6 | 1081 | 4 and plasma | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 7 | 672 | (5 OR 6) and (("CF.sub.4" "SF.sub.6" "NF.sub.3") same (plasma etch\$3)) and (("CF.sub.4" "SF.sub.6" "NF.sub.3") same ("Cl.sub.2" "N.sub.2" "O.sub.2" HBr)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 8 | 223 | 7 and silicide | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |
| 9 | 20 | 8 and (etch\$3 near residue) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB |